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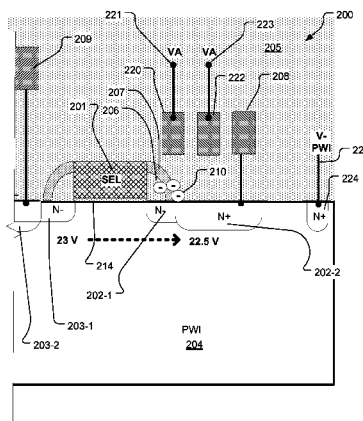
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(57) **ABSTRACT**

A transistor is described including a fly-over conductor. The transistor has a gate, a channel and a source/drain terminal. The fly-over conductor is disposed over the source/drain terminal. A circuit is connected to the fly-over conductor to apply a bias voltage tending to offset effects on the transistor of charge trapped in insulating material. A word line driver can include a transistor with a fly-over conductor.

16 Claims, 7 Drawing Sheets



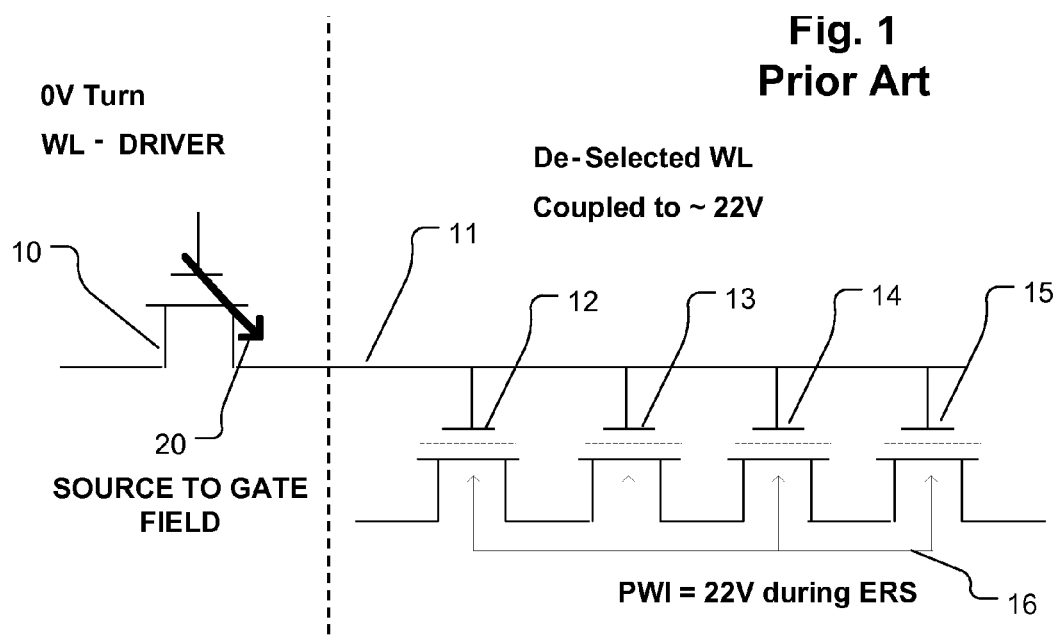
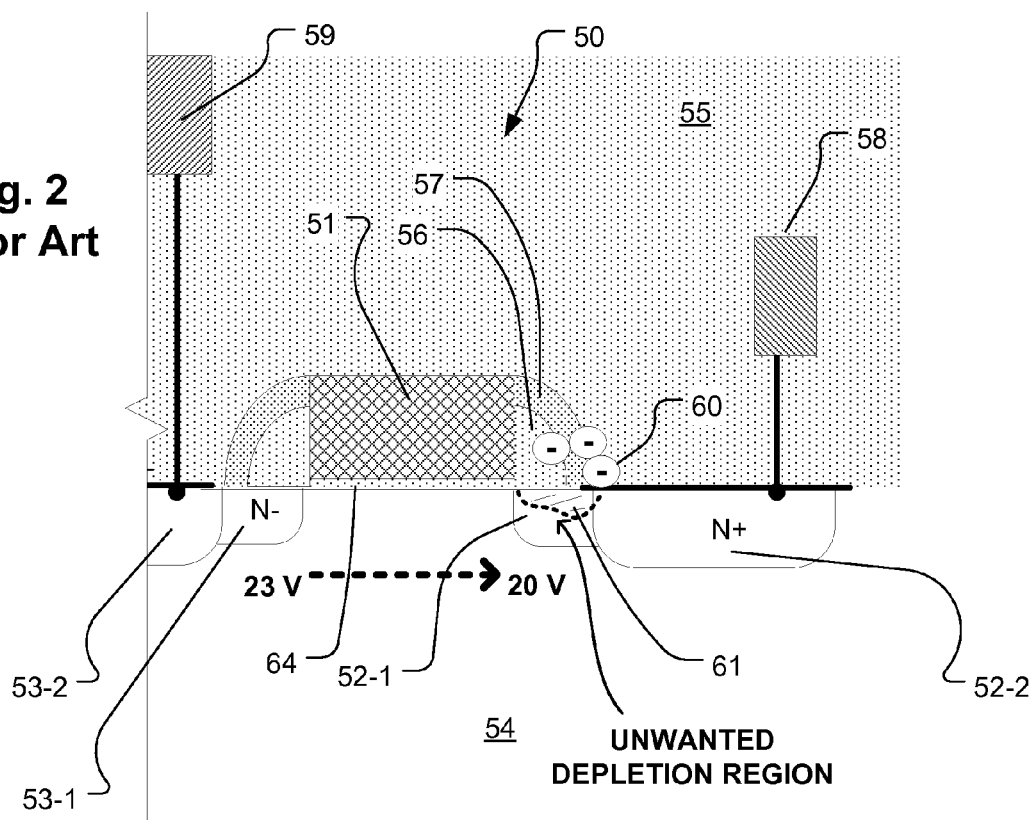


Fig. 2
Prior Art



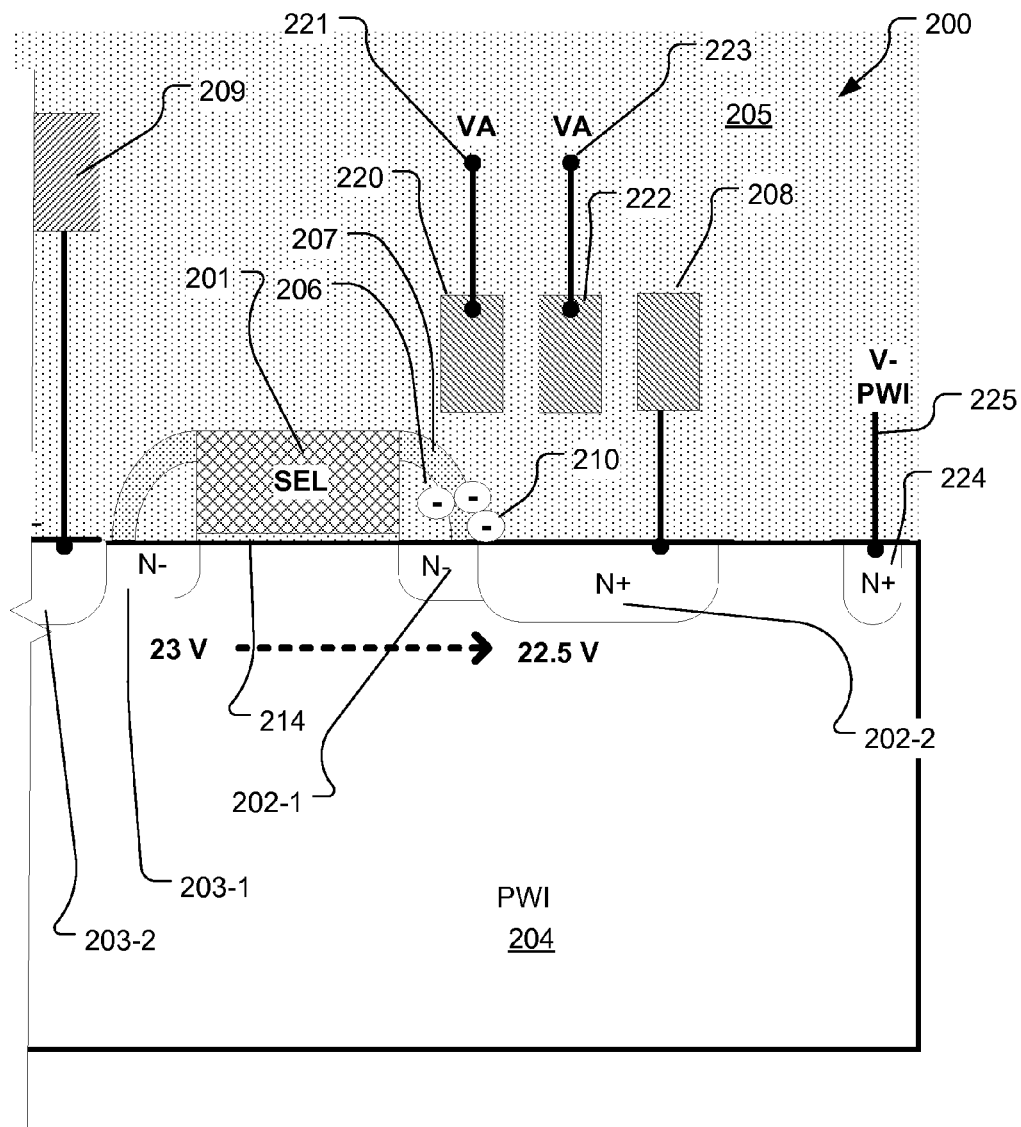


Fig. 3

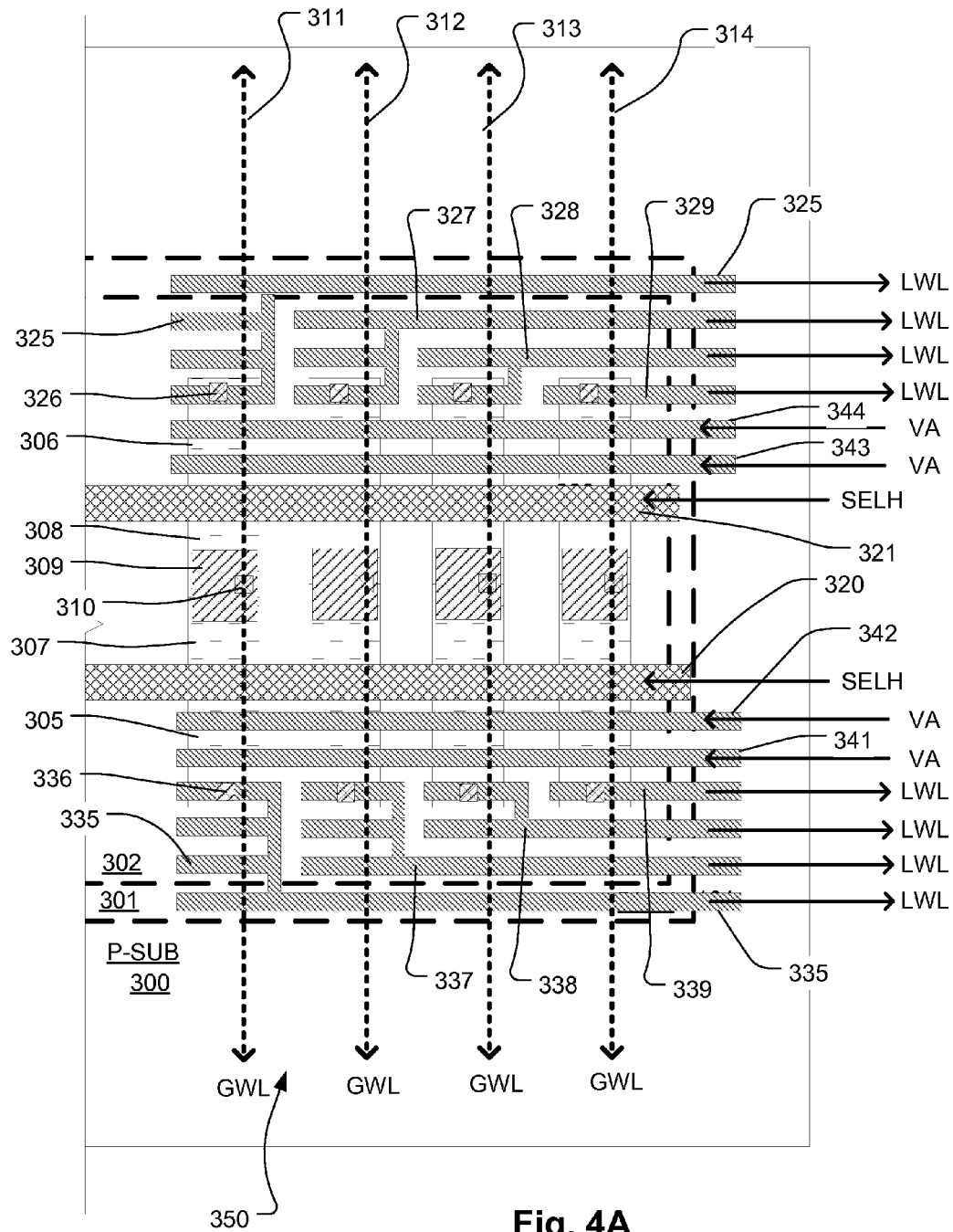


Fig. 4A

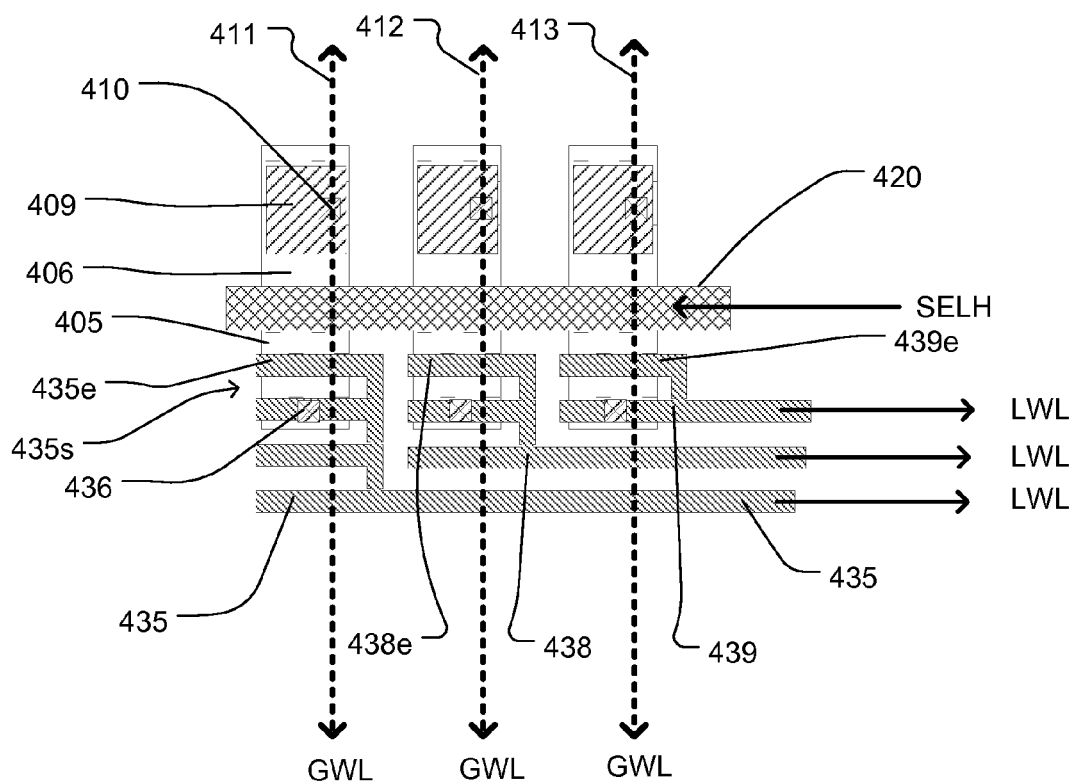


Fig. 4B

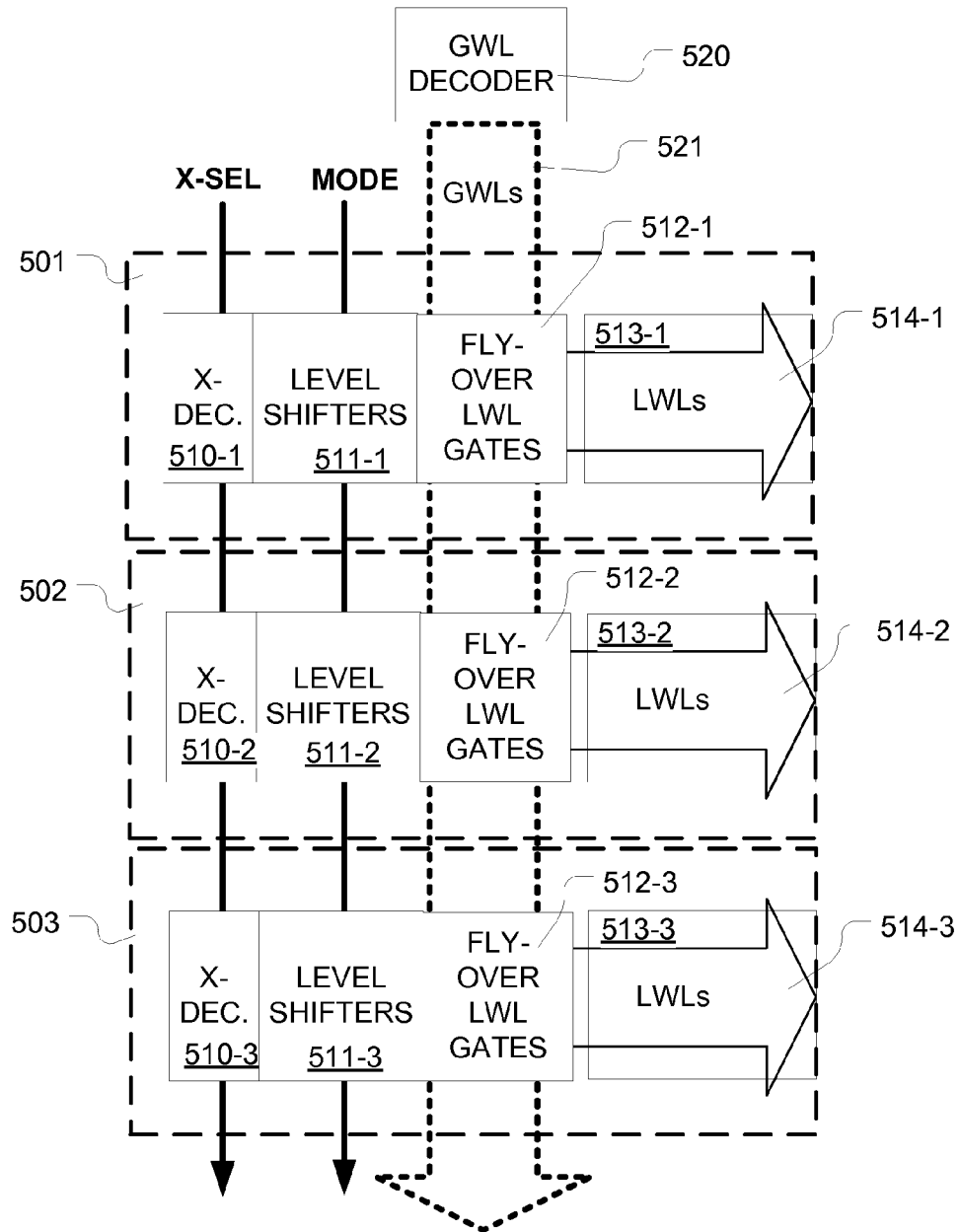
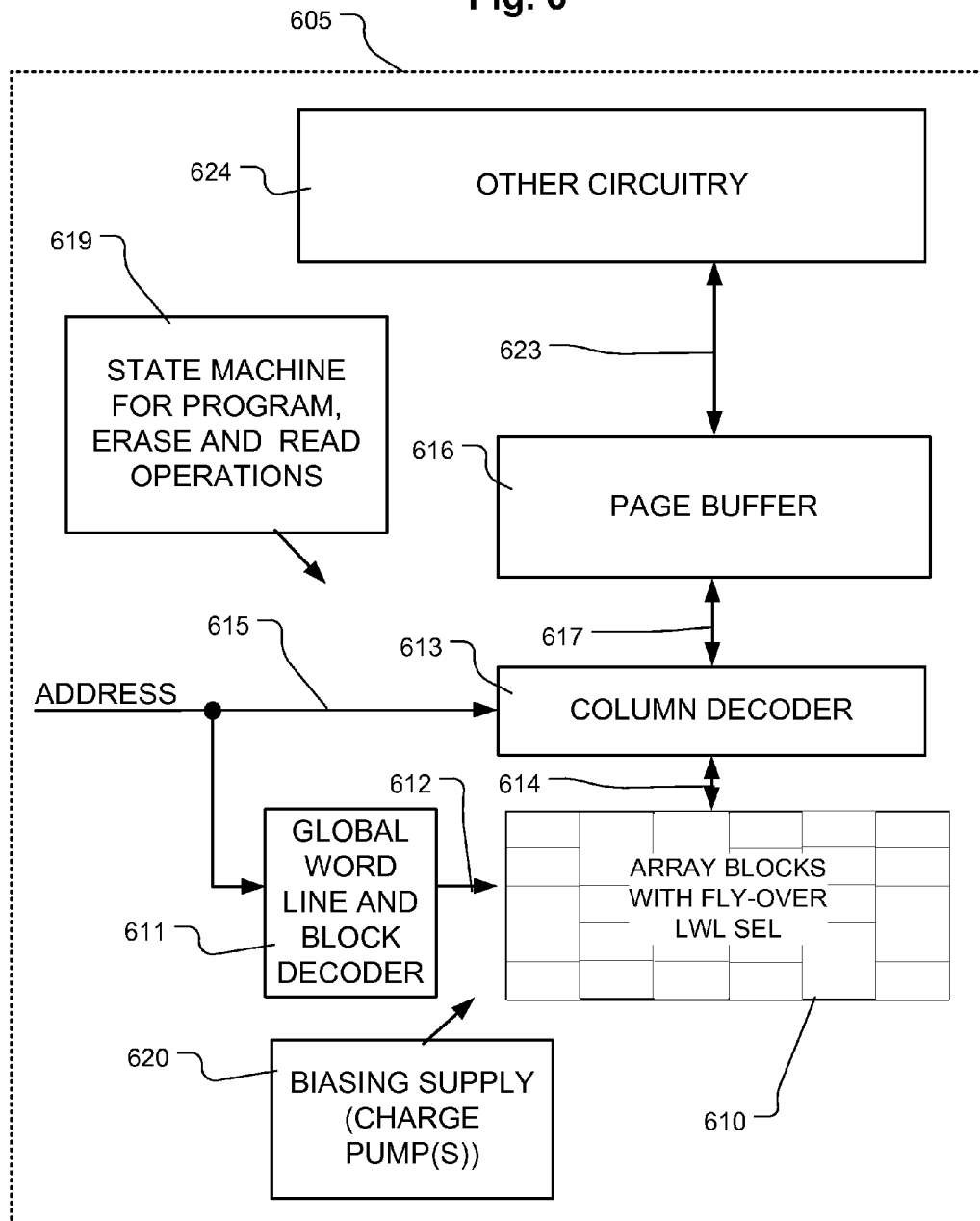
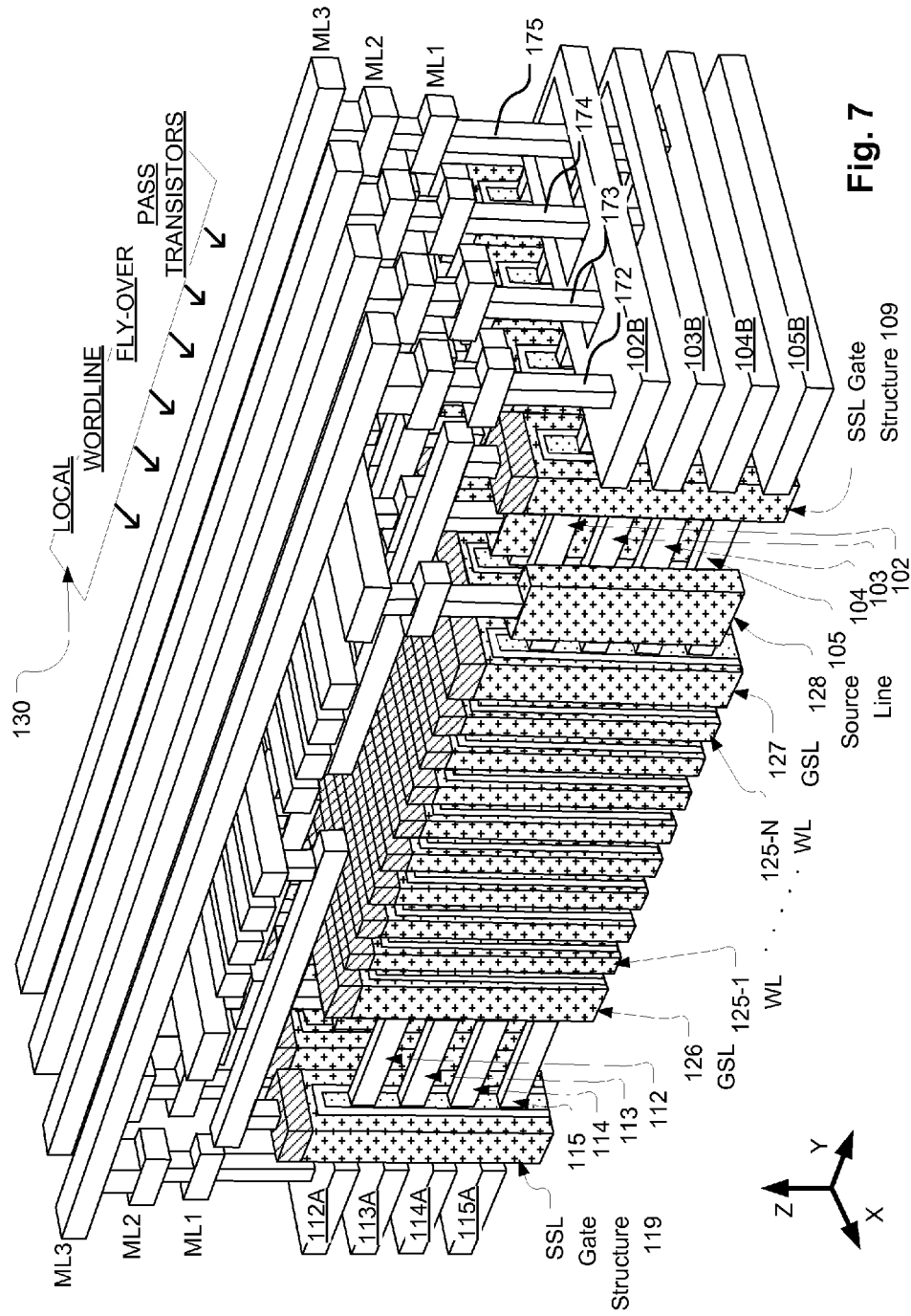


Fig. 5

Fig. 6





TRANSISTOR AND CIRCUIT USING SAME

BACKGROUND OF THE INVENTION

1. Field of the Invention

The present invention relates to transistors in integrated circuits, including transistors suitable for use as high voltage pass transistors like those utilized in some decoding structures for high density memory.

2. Description of Related Art

In high density memory, the arrays of memory cells are often divided into a plurality of blocks of memory cells. Each block of memory cells may include local word lines, requiring corresponding local word line drivers. In these configurations, there can be a global word line driver which drives a set of global word lines for a column of blocks in the array. Each word line in the set of global word lines is set according to the operation being applied to the selected blocks, such as read, program, and erase for high density flash devices. Some operations can require high voltages and some can require negative voltages for some types of memory devices. As a result, word line drivers are required that can meet difficult high voltage and negative voltage operating parameters.

Word line drivers in these environments can include pass transistors which are used to transfer voltages from global word lines to local word lines. These pass transistors can experience high electric fields sufficient to cause unwanted charge trapping in the insulating materials over source/drain terminals. Charge trapped in these locations can create electric fields sufficient to deplete charge carriers in zones near the edges of the channels of the pass transistors. These depletion zones can increase the resistance of the pass transistor when it is operating to transfer voltages. As a result of the increased resistance, a substantial drop in voltage can occur across the device. This drop in voltage can interfere with specified operation of the decoder, and cause other problems.

Transistors utilized in other relatively high voltage environments can experience similar problems.

Thus it is desirable to provide a technology which can address problems arising because of unwanted charge trapping in high voltage transistors, and a technology for deploying such transistors in high density memory devices.

SUMMARY OF THE INVENTION

A transistor is described which is suitable for use in an environment suffering stress caused by unwanted trapped charge in the insulating layers near the gate and source/drain terminal of the transistor. The transistor includes a fly-over conductor over the source/drain terminal, overlying an insulating structure near the gate in which unwanted trapped charge can accumulate. A circuit applies a bias voltage to the fly-over conductor which can offset the effects of unwanted trapped charge.

A memory device is described deploying a transistor including a fly-over conductor in a driver for a row/column line, such as for a local word line.

Manufacturing methods are described for producing a device including a transistor with a fly-over conductor. Also, methods for operating a transistor to suppress the effect of unwanted trapped charge are provided.

Other aspects and advantages of the present invention can be seen on review of the drawings, the detailed description and the claims, which follow.

BRIEF DESCRIPTION OF THE DRAWINGS

FIG. 1 is a schematic diagram illustrating a transistor in a high voltage environment which can cause hot carrier stress and unwanted charge trapping.

FIG. 2 is a cross-section of a prior art pass transistor structure with unwanted trapped charge.

FIG. 3 illustrates a transistor including fly-over conductors as described herein.

FIG. 4A illustrates the layout of a local word line pass transistor structure for a high density memory including fly-over conductors.

FIG. 4B illustrates the layout of a pass transistor structure like that of FIG. 4A showing an alternative configuration of fly-over conductors.

FIG. 5 is a simplified block diagram of a plurality of blocks of a memory array including local word line drivers with pass transistor structures having fly-over conductors.

FIG. 6 is a simplified block diagram of an integrated circuit memory including local word line select circuits with pass transistor structures having fly-over conductors.

FIG. 7 illustrates a block of memory cells in a 3D vertical gate NAND flash array structure, for which the technology described herein can be applied.

DETAILED DESCRIPTION

A detailed description of embodiments of the present invention is provided with reference to the FIGS. 1-7.

FIG. 1 illustrates an environment in the prior art in which high voltage stress induces hot carriers that can cause unwanted charge trapping in a structure over a source/drain terminal of a transistor, such as a multilayer insulator on a side of a gate of the transistor. In this environment, a transistor 10 is utilized as a pass transistor in a word line driver on a memory device. One of the source/drain terminals of the transistor 10 is connected to a word line 11. A plurality of memory cells 12-15 is coupled to the word line 11. The memory cells comprise flash memory cells in this example, such as dielectric charge trapping cells. Some of the operations executed for flash memory cells involved high voltage. For example, in an erase operation for some memory devices, a high voltage, such as for example 22 V, can be applied to the semiconductor body 16 formed for example in an isolated well on an integrated circuit. For a "de-selected" word line, the transistor 10 is off. This causes the word line 11 to adopt a floating state. High voltage in the body 16 can be capacitively coupled to the word line 11 which induces a strong source-to-gate electric field 20. This electric field can induce hot carriers in the source/drain terminal area which can tunnel into insulating material of the multilayer structure used to form a sidewall on the gate, and become unwanted trapped charge.

FIG. 2 illustrates a structure in cross-section of a transistor 50 which could be utilized as the pass transistor 10 in the prior art circuit shown in FIG. 1. The transistor 50 has a gate 51 which overlies a semiconductor body 54. A gate dielectric layer 64 separates the gate 51 from the semiconductor body 54. A first source/drain terminal of the transistor includes a lightly doped region 52-1, and a more heavily doped region 52-2 in the semiconductor body 54. A second source/drain terminal of the transistor includes a lightly doped region 53-1, and a more heavily doped region 53-2 in the semiconductor body 54. The semiconductor body 54 is p-type, and the first and second source/drain terminals are n-type, in

this example, resulting in an n-channel transistor having a structure commonly referred to as an N-MOS or as an n-channel MOSFET.

A conductor **58** is electrically connected to the more heavily doped region **52-2** of the first source/drain terminal by a conductive plug or other interlayer connector. A conductor **59** is electrically connected to the more heavily doped region **53-2** of the second source/drain terminal by a conductive plug or other interlayer connector.

In this example, the gate **51**, the conductor **58**, and the conductor **59** are disposed in different patterned conductor layers on the device. The gate **51** is formed in a patterned polysilicon layer; the conductor **58** is formed in a first patterned metal layer; and the conductor **59** is formed in a second patterned metal layer. Insulating material **55** provides interlayer isolation among the patterned conductor layers. The insulating material includes, in this example, a structure which can trap unwanted charge on the side of the gate **51** and over the more lightly doped region **52-1**. The structure is a multilayer insulating structure in this example including spacer element **56** and spacer element **57** on the side of the gate **51**. The spacer elements **56** and **57** are different insulating materials in this example, that in combination result in a structure that can readily trap charge. This multilayer insulating structure can be a remnant of the manufacturing process used in the formation of interlayer connectors, or other structures. In the illustrated example, the first spacer element **56** comprises silicon dioxide, and the second spacer element **57** comprises silicon nitride.

Unwanted trapped charge **60** is schematically illustrated in the structure, over the first source/drain terminal. This unwanted trapped charge **60** can be trapped in the insulating material **55**, such as in the multilayer insulating structure near the gate **51**, and over the more lightly doped region **52-1** of the first source/drain terminal. The unwanted trapped charge **60** can result in a net negative voltage overlying this region on the transistor, which induces an electric field that can cause an unwanted depletion region **61** in or near the channel of the transistor. This unwanted depletion region **61** can increase the resistivity of the transistor even when the channel is on. Thus, as illustrated, if the transistors being utilized to transfer a high voltage, such as 23 V applied to the second source/drain terminal, a substantial voltage drop can be encountered. Thus, the high voltage is reduced by 3 V in this example, so that only 20 V reaches the first source/drain terminal. Thus, the unwanted trapped charge significantly reduces the driving ability of the transistor.

FIG. 3 illustrates a structure in cross-section of a transistor **200** including fly-over conductors as described herein, which provide immunity against unwanted trapped charge. The transistor **200** has a gate **201** which overlies the semiconductor body **204**. A gate dielectric layer **214** separates the gate **201** from the semiconductor body **54**. In this example, the semiconductor body **204** is an internal p-type well of a triple well structure. The triple well is disposed in a p-type substrate (not shown). A deep n-type well (not shown) is disposed in the substrate. The internal p-type well providing the body **204** is disposed in the deep n-type well. A contact terminal **224** which comprises an n-type doped region is used for connecting the internal p-type well to bias circuits, schematically via line **225**.

A first source/drain terminal of the transistor **200** includes a lightly doped region **202-1**, and a more heavily doped region **202-2** in the body **204**. A second source/drain terminal of the transistor includes a lightly doped region **203-1**, and a more heavily doped region **203-2** in the body **204**. The

body **204** is p-type, and the first and second source/drain terminals are n-type in this example, resulting in an n-channel transistor.

Conductor **208** (output conductor in this example) is electrically connected to the more heavily doped region **202-2** of the first source/drain terminal by conductive plug or other interlayer connector, and provides the voltage transferred by the transistor **200** to a destination structure, such as a word line or other row/column line in a memory array. Conductor **209** (input conductor in this example) is electrically connected to the more heavily doped region **203-2** of the second source/drain terminal by a conductive plug or other interlayer connector, and is coupled to circuitry that provides an input voltage to the transistor **200**.

Fly-over conductors **220** and **222** are disposed over the first source/drain terminal (**202-1**, **202-2**), between the gate **201** and the contact of the plug for output conductor **208** in the source drain terminal. The fly-over conductors **220** and **222** are separated from the first source/drain terminal and from the gate by insulating fill **205**, which can include interlayer dielectric materials.

So, as illustrated in this example, insulating material provides interlayer isolation among the patterned conductor layers as well as other purposes. The insulating material includes, in this example, insulating fill **205**, and a multilayer insulating structure which can readily trap charge, including first spacer element **206** and second spacer element **207** on the side of the gate **201**. The spacer structure can be a remnant of manufacturing processes used in formation of the interlayer connectors, or other structures. In the illustrated example, the first spacer element **206** comprises silicon dioxide, and the second spacer element **207** comprises silicon nitride. Almost any type of dielectric material used as the insulating material can trap charge in some circumstances, and so the technology is not limited to transistors having silicon dioxide and silicon nitride spacer elements.

Unwanted trapped charge **210** is schematically illustrated in the structure, over the first source/drain terminal including trapped charge over the more lightly doped region **202-1**. As discussed above, the unwanted trapped charge can cause an electric field which reduces the driving ability of the transistor **200**. The fly-over conductors **220** and **222** are connected to a fly-over conductor bias voltage generator, which applies a bias voltage **VA** to the fly-over conductors. This bias voltage is to neutralize the electric field induced by the unwanted trapped charge **210** trapped in the insulating material, such as in sidewall spacers **206** or **207**.

The gate **201**, the conductor **208**, and the conductor **209** are disposed in different patterned conductor layers on the device. The gate **201** is formed in a patterned polysilicon layer in this example. The conductor **208** is formed in a first patterned metal layer in this example. The conductor **209** is formed in a second patterned metal layer in this example. In some embodiments, many patterned conductor layers can be disposed on the device, including more than one patterned polysilicon layer in some examples, and more than one patterned metal layer in some examples. The conductors **208** and **209**, and the gate **201** can be disposed in selected layers, or even all in the same layer in some embodiments. In some examples, one or both of the conductors **208** and **209** may be replaced by a diffusion region in the substrate which includes the corresponding more heavily doped region (**202-2**, **203-2**) of the source/drain terminal.

The fly-over conductors **220** and **222** are disposed in the same patterned metal layer as that which includes the output conductor **208** in this example. Thus, the fly-over conductors

220 and **222** can be formed in the same deposition and patterning process as utilized for the output conductor **208**, without an additional processing step.

In this example, two fly-over conductors **220** and **222** are illustrated. The number of fly-over conductors utilized can be selected according to the needs of a particular embodiment. Both, or all, fly-over conductors **220** and **222** are connected to receive the same bias voltage **VA** from a bias circuit, or bias circuits, schematically via lines **221**, **223**, in this example. In other examples, different bias voltages can be applied to the different fly-over conductors disposed for a single transistor. In yet other examples, the fly-over conductors can be electrically connected to, or extensions of, the output conductor **208**. The voltages applied to the fly-over conductors can be tuned as suits the performance needs and structures in a particular embodiment. Also, in other embodiments, a single fly-over conductor may be utilized for a single transistor, and disposed between the gate and the output conductor.

For the purposes of this description, a fly-over conductor is disposed “between” the gate and the output conductor when it is disposed between the structures in layout view, even when they are disposed in different patterned conductor layers. Also, a fly-over conductor can be considered “between” the gate and the output conductor even when the sides of the fly-over conductor may overlap with the sides of the gate, or with the sides of the output conductor, so long as the overlap does not substantially interfere with the operation of the fly-over conductor to induce an electric field to address unwanted trapped charge.

In the illustrated example, the transistor **200** is an n-channel MOSFET. In alternative embodiments, p-channel transistors could be utilized.

The transistor structure shown in FIG. 3 is a triple well structure with the semiconductor channel in an isolated well in the substrate. In other embodiments, the transistor can be a thin film transistor with a semiconductor channel body in a thin film layer isolated from an underlying substrate by a layer of insulating material.

FIG. 4A illustrates in layout view, a pass transistor structure including an array **350** of pass transistors including fly-over conductors, for connecting global word lines to local word lines in a high density memory. In this example, the pass transistors are implemented in a triple well structure to support high voltages and negative voltages applied to local word lines. Thus, for example, the pass transistors are implemented in a p-type substrate **300**. The deep n-type well **301** (illustrated by the dashed line perimeter) is implemented in the substrate **300**. An internal p-type well **302** (illustrated by the dashed line perimeter) is implemented within the deep n-type well **301**. The triple well structure provides isolation of the channel regions of the pass transistors from the grounded substrate.

In this layout, back-to-back pass transistors are illustrated. The pass transistors have gate conductors **320**, **321** connected to a select signal **SEL** which can be generated by a level shifter for the block (See, FIG. 5). Conduction terminals (i.e., source/drain terminals) of the pass transistors are implemented using n-type region (e.g. **305** referring to the leftmost pass transistor in the figure), n-type region (e.g. **306**) and n-type region (e.g. **307**, **308**). The channel regions of the pass transistors are disposed beneath the gate conductors **320**, **321**. An interlayer contact **310** connects the regions **307**, **308** to an overlying conductor layer **309** shown schematically as a single square, but which extends along the GWL line **311** in the figure. An interlayer contact **326**, and an interlayer contact **336** connect the regions **306** and

305 respectively to overlying conductors used as local word line connectors **325** and **335** which are electrically connected and extend to local word lines **LWL**. The conductors used as local word line connectors **325** and **335** include digitated layout features near the contacts **326** and **336**, respectively, which extend laterally from the major axes of the local word line connectors **325** and **335**.

The overlying conductors which comprise the global word lines **311-314** can be implemented in a patterned conductor layer, such as a metal layer on the device.

The array **350** of pass transistors in this example includes four back-to-back pass transistor structures, for a total of eight pass transistors. There are eight corresponding local word line connectors, including local word line connectors **325**, **327**, **328**, **329** in the upper set on the figure, and local word line connectors **335**, **337**, **338**, **339** in the lower set on the figure. The local word line connectors **325**, **327**, **328**, **329** and **335**, **337**, **338**, **339** extend along parallel major axes in the figure for connection to a local word line fanout structure, which may be implemented in a polysilicon layer for example. In some embodiments, the local word line connectors **325**, **327**, **328**, **329** and **335**, **337**, **338**, **339** can be parts of the same patterned conductor (e.g. a polysilicon conductor) that is deployed in the array as a local word line.

The array **350** of pass transistors also includes fly-over conductors **341**, **342**, **343** and **344**. The fly-over conductors **341**, **342** are disposed between the interlayer contact (e.g. **336**) and local word line connector (e.g. **335**) for each transistor in the lower set, and the gate of the transistor which is connected to, or disposed in, the gate conductors **320**. Likewise, the fly-over conductors **343**, **344** are disposed between the interlayer contact (e.g. **326**) and the local word line connectors (e.g. **325**) for each transistor in the upper set, and the gate of the transistor which is connected to, or disposed in, the gate conductor **321**. The fly-over conductors **341**, **342**, **343**, **344** are connected to circuits that apply the bias voltage **VA** as discussed above.

In this embodiment, each of the fly-over conductors is disposed over the source/drain terminals of more than one pass transistor in the array. Also, there are two fly-over conductors disposed over the source/drain terminal of each transistor in the array. In other embodiments, there may be only one fly-over conductor disposed over the source/drain terminal of the transistors in the array. Alternatively, there may be more than two.

In addition, in some embodiments, the fly-over conductors can be connected to separate bias circuitry as mentioned above.

FIG. 4B illustrates, in layout view, a part of a pass transistor structure like that of FIG. 4A, including another example configuration of fly-over conductors. The pass transistors have a gate conductor **420** connected to a select signal **SEL** which can be generated by a level shifter for the block (See, FIG. 5). Conduction terminals (i.e., source/drain terminals) of the pass transistors are implemented using an n-type region (e.g. **405**, referring to the leftmost pass transistor in the figure), and n-type region (e.g. **406**). The channel regions of the pass transistors are disposed beneath the gate conductor **420**. An interlayer contact **410** connects the region **406** to an overlying conductor layer **409** shown schematically as a single square, but which extends along the GWL line **411** in the figure. An interlayer contact **436** connects the region **406** to an overlying conductor used as a local word line connector **435**, which is electrically connected and extends to a local word line **LWL**. The conductor used as a local word line connector **435** includes digitated

layout features near the contact **436**, which extend laterally from the major axis of the local word line connector **435**.

The overlying conductors which comprise the global word lines **411-413** can be implemented in a patterned conductor layer, such as a metal layer on the device.

The connectors **435**, **438**, **439** that act as local word line connectors comprise fly-over conductors in this example consisting of the fingers **435e**, **438e**, **439e** or other forms of extensions on digitated layout features of the word line connectors **435**, **438**, **439**. The word line conductors in this example have digitated layout features which extend laterally from the major axis of the local word line connector **435** with one or more fingers that are parallel to the major axis of the local word line connector **435**. In this embodiment, an interlayer contact (e.g. **436**) is disposed in a position that is at least one finger away from the gate conductor **420** (i.e., a position which has at least one finger between it and the gate conductor **420**). The fingers disposed as fly-over conductors are separated from the other fingers or from the primary local word line connector **435** by an insulating space (e.g. **435s**), and are parallel with the major axis of the local word line connector **435**. These fingers comprise lengths of material that cross over the source/drain region, between the contact **436** and the gate of the transistor in the gate conductor **420**. The fingers **435e**, **438e**, **439e** function as fly-over conductors like the fly-over conductors **341** and **342** of FIG. 4A.

In alternative embodiments, the fly-over conductor can comprise a lateral extension of any practical shape which is part of, or connected by a passive electrical conduction path (i.e. a path without active elements like transistors or diodes) to, the primary conductor (e.g. local word line conductor) that contacts the source drain terminal. The lateral extension is an element which extends outwardly from the side of the conductor where it overlies a contact to the source/drain terminal, as can be defined by an expansion in the extension direction of the width dimension on the major part of the length of the conductor. The extension can overlie the more lightly doped region of the source/drain terminal, overlie a sidewall structure on the side of the gate, or otherwise extend closely enough to the unwanted trapped charge to reduce the effects of the trapped charge on conductivity of the transistor in the ON state.

As a result, the circuits that apply a voltage, such as a high program voltage, to the terminals (e.g. region **406**) of the pass transistors also serve to bias the fly-over conductors. In this example, the pass transistor is circuitry configured to apply a bias voltage to the fly-over conductor, tending to offset effects on the transistor of charge trapped in insulating material. Also, it selectively applies the bias voltage when the transistor is turned on. No additional circuitry is required to bias the fly-over conductors, because they are electrically and passively connected to the output conductors without intervening devices. Other examples can be configured that also electrically connect, using passive or active conduction paths, the fly-over conductors with the output conductors of the devices.

FIG. 5 is a schematic diagram of a plurality of blocks **501-503** in a memory array. Block **501** includes X-DEC circuit **510-1**, level shifter **511-1**, local word line driver **512-1**, including pass transistors having fly-over conductors, and a set **514-1** of local word lines which extend through a subarray **513-1** of memory cells. Block **502** includes X-DEC circuit **510-2**, level shifter **511-2**, local word line driver **512-2**, including pass transistors having fly-over conductors, and a set **514-2** of local word lines which extend through a subarray **513-2**. Block **503** includes X-DEC circuit **510-3**,

level shifter **511-3**, local word line driver **512-3**, including pass transistors having fly-over conductors, and a set **514-3** of local word lines which extend through a subarray **513-3**.

A global word line decoder **520** generates word line voltages for a set of global word lines **521** which extend through the array to the local word line drivers **512-1**, **512-2**, **512-3**, in a set of blocks arranged in a column in the array, or in a set of blocks arranged as desired. The X-DEC circuits (e.g. **510-3**) receive block select signals X-SEL from the block decoder on the integrated circuit, and control enabling the connection of the global word lines to the selected blocks.

The level shifters (e.g. **511-3**) are used to produce control signals for the pass transistors and the fly-over conductors in the local word line drivers, such that the gate voltages on the pass transistors are sufficiently high relative to the word line voltages supplied on the global word lines to turn on the pass transistors in selected blocks, and the bias voltages on the fly-over conductors are sufficient to suppress depletion in the pass transistors that could be caused by unwanted trapped charge.

The level shifters can be configured to provide both the control signals for the pass transistors and for the fly-over conductors in response to the X-DEC circuit. In this case, the bias voltages are selectively applied, to turn on and off the pass transistor, and to apply the potential VA to the fly-over conductors when the pass transistor is on. In some embodiments, the potential applied to the fly-over conductor is reduced when the pass transistor is off. Alternatively, the fly-over conductor can be left in floating condition in some circumstances. In yet other embodiments, the potential VA can be applied to the fly-over conductors whenever the memory array is in use, independent of the decoding.

Also, the potential VA applied to the fly-over conductors can be a constant. In other examples, potential VA can vary with time or with the type of operation being executed using the local word line.

In other embodiments, circuits used to apply the bias potential VA can be independent of the level shifters, and disposed on the integrated circuit in positions chosen according to the layout of the particular embodiment.

In some implementations, such as in flash memory, the word line voltages can exceed 20 volts or more during program or erase operations. In such implementations, the level shifters are coupled with charge pumps or other high voltage sources to produce select signals that can be about 5 volts or more higher than the word line voltages, or 25 volts or more. Thus, the pass transistors utilized for the local word lines have breakdown voltages sufficiently high for reliable operation at such high voltages.

FIG. 6 is a simplified block diagram of an integrated circuit **605** including a memory array **610** including a plurality of blocks of memory cells, each block including a subarray of memory cells with local word lines. The blocks in this example include, or are coupled with, local word line select transistors, with fly-over conductors configured to reduce the effects of unwanted trapped charge that can arise due to hot carrier stress.

A word line and block decoder **611** drives global word lines and block decode lines (collectively, **612**), arranged in the memory array **610**. The global word lines supply word line voltages to the local word lines in blocks selected by the block decode lines. In embodiments described herein, each block includes circuits to connect the global word lines to corresponding local word lines using pass transistors disposed in the word line drivers of the local word lines.

A column decoder **613** is coupled to a plurality of global bit lines **614** arranged along columns in the memory array **610** for reading data from and writing data to the memory array **610**. Addresses are supplied on bus **615** to decoder **611** and decoder **613**. Page buffer circuits **616**, including one or more buffers and associated circuitry, are coupled to the column decoder **613**, in this example via data lines **617**.

The page buffer circuits **616** can be coupled via lines **623** to input/output circuits and other data sources internal or external (collectively "other circuitry" **624**) to the integrated circuit **605**, such as a general purpose processor or special purpose application circuitry, or a combination of modules providing system-on-a-chip functionality supported by the memory array **610**.

In the example shown in FIG. 6, control logic **619** controls the application of supply voltages generated or provided through the voltage supply or supplies in biasing supply circuits **620**, such as read, erase, verify and program bias voltages, including voltages on global word lines, bit lines, block select lines and other bias points used in accessing the memory cells storing data in the array. The application of voltages applied to the fly-over conductors is also controlled by a circuit, which can be considered part of the control logic **619** in the example represented by FIG. 6. The voltages applied to the fly-over conductors can be produced using biasing supply circuits **620** on the integrated circuit **605**.

FIG. 7 is a perspective illustration of a block of memory cells of a three-dimensional (3D) integrated circuit device, which provides one example of a block including a subarray of memory cells of an array (such as array **610** in FIG. 6), and is suitable for use in a product like that represented by FIG. 6.

The device illustrated in FIG. 7 includes a plurality of stacks of active strips acting as channel lines in NAND strings, alternating with insulating strips. Insulating material is removed from the drawing to expose additional structure. For example, insulating strips are removed between the active strips in the stacks, and are removed between the stacks of active strips. This structure is described herein in some detail, as an example of a three-dimensional (3D) memory array which can be manufactured on a semiconductor substrate, in combination with peripheral circuits on the substrate (not shown), including local word line drivers and a fanout structure for connection of the local word lines to the local word line drivers (represented by block **130**) having high voltage pass transistors with fly-over conductors as described herein.

In the example shown in FIG. 7, a multilayer array is formed on an insulating layer, and includes a plurality of local word lines **125-1** WL through **125-N** WL conformal with the plurality of stacks. The local word lines extend to the structure **130**, at which word line voltages from global word lines are supplied to the corresponding local word lines in the block using pass transistors with fly-over conductors biased to neutralize effects of unwanted trapped charge as discussed above.

The plurality of stacks includes active strips **112**, **113**, **114**, and **115** in multiple planes. Active strips in the same plane are electrically coupled together by contact pads (e.g. **102B**).

A contact structure including a stack of contact pads **112A**, **113A**, **114A**, and **115A** terminate active strips, such as the active strips **112**, **113**, **114**, and **115** in the plurality of stacks. As illustrated, these contact pads **112A**, **113A**, **114A**, and **115A** are electrically connected to different bit lines for connection to decoding circuitry to select planes within the

array. These contact pads **112A**, **113A**, **114A**, and **115A** can be patterned at the same time that the plurality of stacks is defined.

A contact structure including a stack of contact pads **102B**, **103B**, **104B**, and **105B** terminate active strips, such as active strips **102**, **103**, **104**, and **105**. As illustrated, interlayer connectors **172**, **173**, **174**, **175** electrically connect contact pads **102B**, **103B**, **104B**, and **105B** to different bit lines in metal layers, such as a metal layer **ML3**, for connection to decoding circuitry to select planes within the array. The stack of contact pads **102B**, **103B**, **104B**, and **105B** can be patterned at the same time that the plurality of stacks is defined.

In this example, any given stack of active strips is coupled to either the stack of contact pads **112A**, **113A**, **114A**, and **115A**, or the stack of contact pads **102B**, **103B**, **104B**, and **105B**, but not both. The stack of active strips **112**, **113**, **114**, and **115** is terminated at one end by the stack of contact pads **112A**, **113A**, **114A**, and **115A**, passes through SSL gate structure **119**, ground select line **GSL 126**, local word lines **125-1** WL through **125-N** WL, ground select line **GSL 127**, and is terminated at the other end by source line **128**. The stack of active strips **112**, **113**, **114**, and **115** does not reach the stack of contact pads **102B**, **103B**, **104B**, and **105B**.

The stack of active strips **102**, **103**, **104**, and **105** is terminated at one end by the stack of contact pads **102B**, **103B**, **104B**, and **105B**, passes through SSL gate structure **109**, ground select line **GSL 127**, local word lines **125-N** WL through **125-1** WL, ground select line **GSL 126**, and is terminated at the other end by a source line (obscured by other parts of the figure). The stack of active strips **102**, **103**, **104**, and **105** does not reach the stack of contact pads **112A**, **113A**, **114A**, and **115A**.

A layer of memory material is disposed in interface regions at cross-points between surfaces of the active strips **112-115** and **102-105** and the plurality of local word lines **125-1** WL through **125-N** WL. In particular, the layer of memory material is formed on side walls of the active strips in the plurality of stacks. Ground select lines **GSL 126** and **GSL 127** are conformal with the plurality of stacks, similar to the local word lines.

Every stack of active strips in this example is terminated at one end by contact pads and at the other end by a source line. For example, the stack of active strips **112**, **113**, **114**, and **115** is terminated at one end by contact pads **112A**, **113A**, **114A**, and **115A**, and terminated on the other end by a source line **128**. At the near end of the figure, every other stack of active strips is terminated by the contact pads **102B**, **103B**, **104B**, and **105B**, and every other stack of active strips is terminated by a separate source line. At the far end of the figure, every other stack of active strips is terminated by the contact pads **112A**, **113A**, **114A**, and **115A**, and every other stack of active strips is terminated by a separate source line.

Bit lines and string select gate structures are formed at the metals layers **ML1**, **ML2**, and **ML3**. Bit lines are coupled to a plane decoder (not shown). String select gate structures are coupled to a string select line decoder (not shown).

The ground select lines **GSL 126** and **127** can be patterned during the same step that the local word lines **125-1** WL through **125-N** WL are defined. In some embodiments, a ground select line decoder can include pass transistors with fly-over conductors. Ground select devices are formed at cross-points between surfaces of the plurality of stacks and ground select lines **GSL 126** and **127**. The SSL gate structures **119** and **109** can be patterned during the same step in which the local word lines **125-1** WL through **125-N** WL are defined. In some embodiments, the string select line decoder

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can include pass transistors with fly-over conductors. String select devices are formed at cross-points between surfaces of the plurality of stacks and string select (SSL) gate structures 119 and 109. These devices are coupled to decoding circuitry for selecting the strings within particular stacks in the array.

Although the subarray shown in FIG. 7 is representative of a block of flash memory cells in a 3D NAND configuration suitable for use with the technology described herein for connecting global word lines to local word lines, other memory structures can be utilized, including other configurations of 3D vertical gate structures, 3D vertical channel structures, 2D arrays, arrays in NOR configurations, arrays in AND configurations and other memory structures. Also, other memory cell technologies can be utilized, including all types of volatile and nonvolatile memory suitable for arrangement in blocks with local word lines as described herein.

A method for manufacturing a transistor with a fly-over structure is therefore provided. The method includes forming a transistor having a gate, a channel and a source/drain terminal. A fly-over conductor is disposed over the source/drain terminal, with insulating material electrically insulating the fly-over conductor from the source/drain terminal. A circuit is formed that is connected to the fly-over conductor to apply a bias voltage tending to neutralize an electric field induced by charge trapped in the insulating material. In addition, a circuit can be provided that is connected to the gate of the transistor to apply a gate voltage to selectively turn on and turn off the transistor.

A method for operating a transistor is described. The method includes applying a gate voltage to selectively control transfer of a voltage from an input side source/drain terminal to an output side source/drain terminal of the transistor, and inducing an electric field over the output side source/drain terminal tending to neutralize an electric field induced by charge trapped in insulating material over the output side source/drain terminal by, for example, using a fly-over conductor.

The transistor structure described herein, including fly-over conductors, is suitable for use in local word line drivers for high density memory as discussed above. In addition, the transistor structure can be deployed in other environments, including low voltage and high voltage applications, in which unwanted trapped charge can affect the drive ability of the transistor.

The technology can be deployed with a simple modification of the layout of a patterned metal layer, along with the addition of circuitry for biasing the fly-over conductors. This enables deployment of the technology for very low cost, and with very little layout penalty.

While the present invention is disclosed by reference to the preferred embodiments and examples detailed above, it is to be understood that these examples are intended in an illustrative rather than in a limiting sense. It is contemplated that modifications and combinations will readily occur to those skilled in the art, which modifications and combinations will be within the spirit of the invention and the scope of the following claims.

What is claimed is:

1. A device comprising:

a transistor having a gate, a channel under the gate and a first source/drain terminal, the channel being doped with impurities that establish a first conductivity type, and the first source/drain terminal being doped with impurities that establish a second conductivity type different from the first conductivity type, wherein the

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first source/drain terminal includes a more lightly doped region and a more heavily doped region;
a fly-over conductor disposed over the first source/drain terminal, separated from the first source/drain terminal and from the gate by insulating material, and laterally spaced away from the gate and the channel;
a circuit including the transistor connected to the fly-over conductor to apply a bias voltage tending to offset effects on the transistor of charge trapped in the insulating material; and

an output conductor is connected to the first source/drain terminal, wherein the fly-over conductor is a lateral extension of the output conductor, which at least partly overlies the more lightly doped region.

2. The device of claim 1, wherein the circuit connected to the fly-over conductor selectively applies the bias voltage when the transistor is turned on.

3. The device of claim 1, wherein the transistor includes a second source/drain terminal and a circuit connected to the second source/drain terminal to apply a voltage to the second source/drain terminal, and the transistor transfers the voltage from the second source/drain terminal to the first source/drain terminal when the transistor is turned on.

4. The device of claim 1, including an array of transistors, the array including said transistor, and wherein the fly-over conductor is disposed in a pattern so that it passes over first source/drain terminals in more than one of the transistors in the array.

5. The device of claim 1, wherein the transistor includes a second source/drain terminal, and further including:

a memory array having global word lines and local word lines; and

a circuit connected to the second source/drain terminal to apply a voltage being transferred from the second source/drain terminal to the first source/drain terminal when the transistor is turned on, the first source/drain terminal being electrically connected to a local word line in the array and the second source/drain terminal being electrically connected to a global word line in the array.

6. The device of claim 1, wherein the fly-over conductor is passively electrically connected to the output conductor, and the circuit that applies a bias voltage to the fly-over conductor is connected to the output conductor.

7. The device of claim 1, wherein the gate includes a sidewall structure, and wherein the fly-over conductor at least partly overlies the sidewall structure.

8. A device comprising:

a substrate;

an array of memory cells on the substrate, including a row/column line;

a transistor having a gate, a first source/drain terminal, a channel under the gate and a second source/drain terminal, the channel being doped with impurities that establish a first conductivity type, and the first source/drain terminal being doped with impurities that establish a second conductivity type different from the first conductivity type, the row/column line being electrically connected to the first source/drain terminal, wherein the first source/drain terminal includes a more lightly doped region and a more heavily doped region;
a fly-over conductor disposed over the first source/drain terminal and laterally spaced away from the gate and the channel, and separated from the first source/drain terminal and from the gate by insulating material,

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wherein the fly-over conductor is a lateral extension of the row/column line, which at least partly overlies the more lightly doped region;

a select line including, or connected to, said gate;

a bias voltage generator which applies a bias voltage to the fly-over conductor tending to neutralize an electric field induced by charge trapped in the insulating material; and

a row/column line select signal generator which produces a select signal, connected to the select line.

9. The device of claim 8, including a plurality of transistors, including said transistor, and wherein the array includes a plurality of blocks of memory cells, said row/column line being one of a plurality of local word lines disposed in one of the blocks, and the local word lines in the plurality of local word lines being electrically connected to corresponding transistors in the plurality of transistors.

10. The device of claim 9, including a row/column line voltage generator with connections to second source/drain regions in the plurality of transistors, and the word line row/column line voltage generator generating voltages for corresponding ones of the plurality of local word lines.

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11. The device of claim 10, wherein the row/column line voltage generator comprises a global word line driver coupled to transistors in the plurality of blocks.

12. The device of claim 8, wherein the row/column line select signal generator includes a level shifter, and produces the select signal at a voltage level sufficient as compared to a voltage on the row/column line, to turn on the transistor when the row/column line is selected.

13. The device of claim 8, wherein said array comprises a 3D array.

14. The device of claim 8, including a connecting line having a major axis extending to the row/column line, and having a digitated layout feature extending laterally from the major axis and an interlayer contact, connecting the digitated layout feature with the first source/drain terminal.

15. The device of claim 8, wherein the fly-over conductor is passively and electrically connected to the row/column line, and the bias voltage generator is connected to the second source/drain terminal.

16. The device of claim 8, wherein the gate includes a sidewall structure, and the fly-over conductor at least partly overlies the sidewall structure.

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